

Notice of References Cited	Application/Control No. 10/764,023	Applicant(s)/Patent Under Reexamination PARK ET AL.	
	Examiner Jacques M. Saint-Surin	Art Unit 2856	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,283,037	02-1994	Baer et al.	422/82.01
*	B	US-6,452,310	09-2002	Panasik, Carl M.	310/334
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Storming Media, Reactive Ion Etching of PECVD Silicon Dioxide (SiO ₂) Layer for MEMS application, July 2004.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.